

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) An alignment apparatus, comprising:

a position detection optical system which detects a position of a mark formed on a street line of a substrate; and

a focus detection system which irradiates a detection light to the substrate, and which detects deviation between an irradiated region and a focus plane ~~focused surface~~ of the position detection optical system by detecting a reflected light of the detection light, the detection light ~~is being~~ irradiated on a region of said street line ~~on which~~ is different from a region on which ~~formed~~ said mark is formed.
2. (Currently Amended) The alignment apparatus as set forth in claim 1, wherein:

said street line exists in a first direction and in a second direction perpendicularly crossing with the first direction; and

said focus detection system comprises a first detection system using a first detection light extending along ~~with~~ said first direction and a second detection system using a second detection light extending along ~~with~~ said second direction.
3. (Currently Amended) The alignment apparatus as set forth in claim 2, wherein at least one of said first and second detection systems detects a plurality of portions on said street ~~lines~~line.
4. (Currently Amended) The alignment apparatus as set forth in claim 2, wherein said focus detection system makes a comparison of intensities of reflection lights of said first

5. (Currently Amended) The alignment apparatus as set forth in claim 2, wherein said focus detection system performs focus detection by using said first detection system when a street line on which a mark for position detection exists is along said first direction, and by using said second detection system when the street line is along said second direction.

6. (Currently Amended) An exposure apparatus wherein a predetermined pattern is ~~exposed~~ to be transferred is exposed onto a substrate which is aligned by the alignment apparatus as set forth in claim 1.

7. (Currently Amended) An alignment method for aligning a substrate on which a mark is formed on a street line, including the steps of:

irradiating a detection light on a region on said street line before detecting a position of the mark by a position detection optical system, the region is being different from a region on which ~~formed~~ said mark is formed;

detecting deviation between an irradiated region and a ~~focused surface~~ focus plane of said position detection optical system by detecting a reflected light of the detection light.

8. (Currently Amended) The alignment method as set forth in claim 7, wherein:
said street line exists in a first direction and a second direction perpendicularly crossing with the first direction; and

a first detection light extending along ~~with~~ said first direction and a second detection light extending along ~~with~~ said second direction are irradiated as said detection lights.

9. (Original) The alignment method as set forth in claim 8, wherein intensities of

comparison result.

10. (Currently Amended) The alignment method as set forth in claim 8, wherein focus detection is performed by using said first detection light when a street line on which a mark for position detection exists is along said first direction, and by using said second detection light when the street line is along said second direction.

11. (Original) An exposure method, including the steps of:
aligning a photosensitive substrate as an object to be exposed by using the alignment method as set forth in claim 7; and
exposing the aligned photosensitive substrate with a pattern formed on a mask.